



Form 1449 (Modified)	Atty Docket No. NOVLP078/NVLS2856	Application No.: 10/670,660
<b>Information Disclosure Statement By Applicant</b>	Applicant: Yu, et al.	
(Use Several Sheets if Necessary)	Filing Date September 24, 2003	Group <b>2823</b> <del>Unassigned</del>

#### U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A						
	B						

#### Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
	C							
	D							
	E							
	F							
	G							

#### Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
BKR	H	Masahiko Maeda, et al., "A Low-Permittivity Interconnection Using an SiBN Interlayer", September 1989, IEEE Transactions on Electron Devices, Vol. 36, No. 9.
BK	I	Takashi Sugino, et al., "Synthesis of boron nitride film with low dielectric constant for its application to silicon ultralarge scale integrated semiconductors", 2001 Elsevier Science B.V., Diamond and Related Materials 1275-1379.
Examiner <b>Bv. Kerman</b>		Date Considered <b>01/21/05</b>

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



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BK	A	Yu, et al., "Low-K B-Doped SIC Copper Diffusion Barrier Films", Novellus Systems, Inc., Appln No. 10/915,117, filed August 9, 2004, pages 1-22. ( <del>Atty Docket No. NOVLP101/NVLS-2915</del> ) .
Examiner <i>Bv. Keman</i>		Date Considered 01/31/05

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